

METHOD AND APPARATUS FOR IMPROVED FOCUS RING

ABSTRACT OF THE DISCLOSURE

A focus ring assembly, configured to be coupled to a substrate holder in a plasma processing system, comprises a focus ring having one or more wear indicators for determining the lifetime of the focus ring, wherein the coupling of the focus ring to the substrate holder facilitates auto-centering of the focus ring in the plasma processing system. For example, a centering ring mounted on the substrate holder can comprise a centering feature configured to couple with a mating feature on the focus ring.